

Nikon NSR-2205il2D

Lamp Illumination Uniformity

2019-12-19 19:18

Lamp Illumination Uniformity

Condition File: 22LAMP.LMCP
Result File: 2020-0206-LAMP.LAMP
Machine ID: AF28012
Date: 2020-02-18 08:35:43
Comment: LAMP Illumination Uniformity (11*13)

Measurement Condition

Illumination ID: 2
Intra-field Repeat Count: 1
Map Layout
X: 11
Y: 13
Diameter: 31.11 [mm]
Measurement Limits
-X: -11000.00 [μm]
+X: 11000.00 [μm]
-Y: -12700.00 [μm]
+Y: 12500.00 [μm]
Power Trans. Rate: 1.22
Sensor Position
X: 130466.00 [μm]
Y: 77425.00 [μm]
Average Number: 1
Step Mode: Normal
Dummy Shot
Blind Setting: Pinhole
Frequency: 10
Time: 100 [msec]
Wait Time: 100 [msec]

Measurement Result Summary

Maximum: 917.819 [mW/cm²]
Minimum: 891.785 [mW/cm²]
Average: 901.817 [mW/cm²]
Uniformity: 1.439 [%]

Intra-field Repeat No. 1

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F6 Param. F10 Map F14 Exit

Help

Ver2.51A

◆ Exposure

▼ Shot Information

PAUSE

RESUME

STOP

HELP

COMMUNICATE

Wafer Flatness

MCSV : EVALUATE - Local Flatness

Wafer Flatness

Meas. Proc.Prog. : FCWAFLAT.WFLAT
Condition File : FCWAFLAT.WFCP
Result File : WFLAT.WFLT
Machine ID : AF28012
Date : 2020-02-18 19:05:24
Comment : Wafer Flatness (7.5mm pitch)

Measurement Condition		Measurement Result	
Map Layout X :	17	Base Plane :	Stage
Y :	17	Max. :	0.533 [μm]
Step Pitch X :	7500.000 [μm]	Min. :	-0.863 [μm]
Y :	7500.000 [μm]	Max.-Min. :	1.397 [μm]
Map Offset X :	0.000 [μm]	Approximated Plane	
Y :	0.000 [μm]	Angle X :	4.205 [μrad]
Image Plane X :	0.000 [μrad]	Angle Y :	-4.086 [μrad]
Y :	0.000 [μrad]	App. Plane-Image Plane	
Leveling : OFF		Angle X :	4.205 [μrad]
Leveling Offset X :	0.000 [μrad]	Angle Y :	-4.086 [μrad]
Y :	0.000 [μrad]		

Local Flatness Simulation
L.F.S. Mode : 3-Cross
Max. : 0.427 [μm]

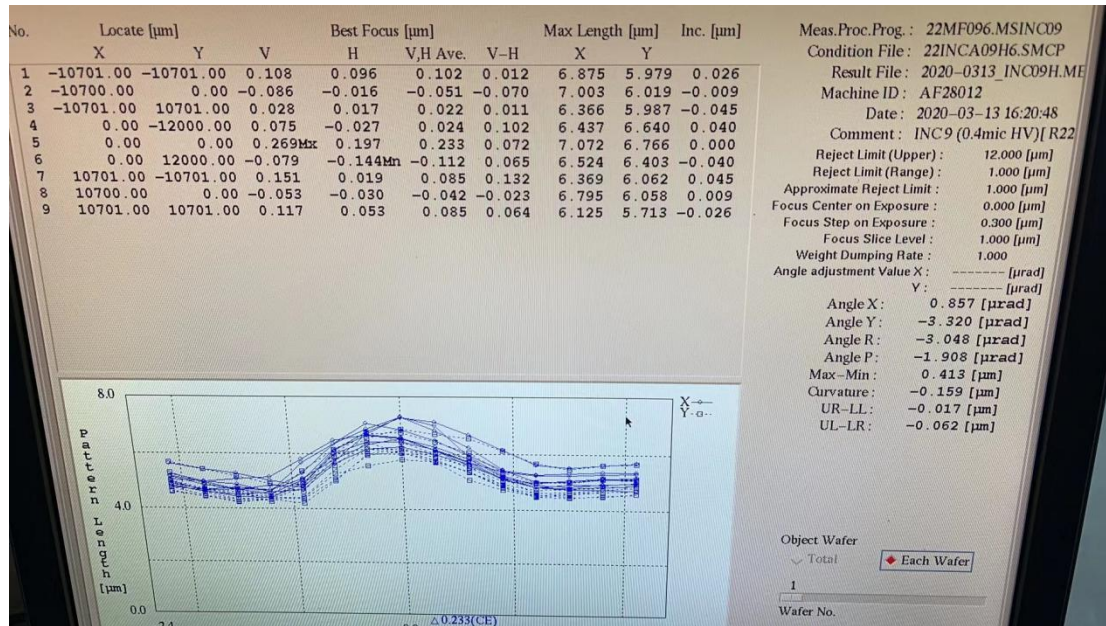
1
Wafer No.

Prev Next

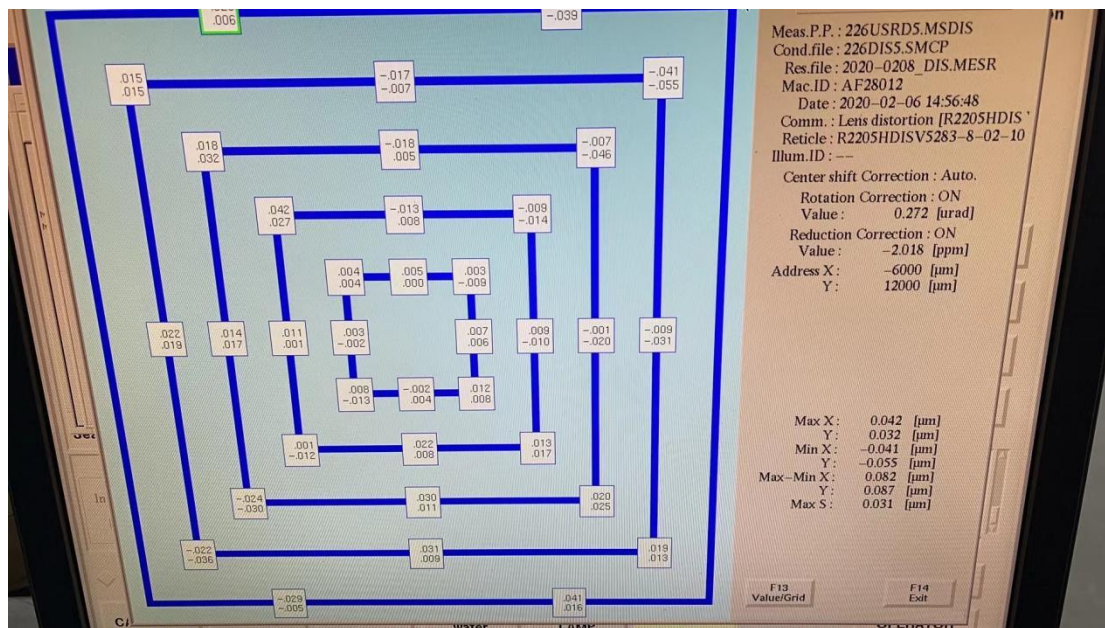
F6 Param. F9 L.F. map F10 W.F. map F14 Exit

CALIBRATE machine MANUAL operation MEASURE wafers measure wafer FLATNESS measure LAMP illumination

lens inc



lens dis



Stepping

